



PTO/SB/08a (07-05)

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**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

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Complete if Known

Application Number	10/765,223
Filing Date	01/26/2004
First Named Inventor	Smith et al
Art Unit	1756
Examiner Name	C. Young
Attorney Docket Number	38203-6081B

U. S. PATENT DOCUMENTS

Examiner Initials*	Cite No. ¹	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code ² (if known)			
CY		US- 4,757,207	07/1988	Chappelow et al	
		US- 4,861,148	08/1989	Sato et al	
		US- 4,929,083	05/1990	Brunner	
		US- 5,124,927	06/1992	Hopewell et al	
		US- 5,262,257	11/1993	Fukuda et al	
		US- 5,285,236	02/1994	Jain	
		US- 5,438,413	08/1995	Mazor et al	
		US- 5,444,538	08/1995	Pellegrini	
		US- 5,477,058	12/1995	Sato	
		US- 5,700,602	12/1997	Dao et al	
		US- 5,757,507	05/1998	Ausschnitt et al	
		US- 5,805,290	09/1998	Ausschnitt et al	
		US- 5,824,441	10/1998	Farrow et al	
		US- 5,877,861	03/1999	Ausschnitt et al	
		US- 5,953,128	09/1999	Ausschnitt et al	
		US- 6,023,338	02/2000	Bareket	
CY		US- 6,064,486	05/2000	Chen et al	
		US- 6,079,256	06/2000	Bareket	

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CY		US- 6,130,750	10/2000	Ausschnitt et al	
		US- 6,137,578	10/2000	Ausschnitt	
		US- 6,142,641	11/2000	Cohen et al	
		US- 6,143,621	11/2000	Tzeng et al	
		US- 6,153,886	11/2000	Hagiwara et al	
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		US- 6,204,912	03/2001	Tsuchiya et al	
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		US- 6,417,929	07/2002	Ausschnitt et al	
		US- 6,737,207	05/2004	Imai	
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		US- 6,734,971	05/2004	Smith et al	
		US- 6,906,303	06/2005	Smith	
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NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
CY		Armitage et al, Analysis of overlay distortion patterns, SPIE Vol. 921, 207:221, 1988	
		Biesterbos et al., A New Lens for Submicron Lithography and its Consequences for Wafer Stepper Design, SPIE Vol. 633, Optical Microlithography V, 34:43, 1986	
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Application Number 10/765,223

Filing Date 01/26/2004

First Named Inventor Smith et al

Art Unit 1756

Examiner Name C. Young

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Attorney Docket Number 38203-6081B

NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
CY		Handbook of Microlithography, Micromachining and Microfabrication, Book: Vol. 1, "Microlithography", Rai-Choudhury, P. (Ed.), SPIE Optical Engineering Press, SPIE, Bellingham, Washington, pp. 417-418 (1997)	
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		Lin, "The Attenuated Phase-Shifting Mask", Solid State Technology, Special Series/Advanced Lithography, 35(1): 43-47 (1992)	
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First Named Inventor Smith et al

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CY		McFadden, C. et al, A Computer Aided Engineering Workstation for Registration Control, SPIE Vol. 1087, 255:266, 1989	
		Mulkens et al., ArF Step and Scan Exposure System for 0.15 Micron and 0.13 Micron Technology Node, SPIE Conference on Optical Microlithography XII, 506:521, March 1999	
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		Press et al., Numerical Recipes, The Art of Scientific Computing, Cambridge University Press, 509:520, 1990.	
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CY		Quaestor Q7, "Fully Automated Optical Metrology System for Advanced IC Production", Quaestor Q7 Product Specification, BIO-RAD 2 pages	
		Raugh, "Error Estimation for Lattice Methods of State Self-Calibration", SPIE, 3050:614-625 1997	
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		Starikov, "Metrology of Image Placement", Handbook of Silicon Semiconductor Metrology, pp. 411-475, 2001	
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		M. van den Brink et al., "Matching Management of Multiple Wafer Steppers Using a Stable Standard and a Matching Simulator", Proc. of SPIE, Vol. 1087, pp. 218-232, 1989	
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CY		van den Brink et al, New 0.54 Aperture I-Line Wafer Stepper with Field by Field Leveling Combined with Global Alignment, SPIE Vol. 1463, 709:724, 1991	
		van den Brink et al., Step and Scan and Step and Repeat, a Technology Comparison, SPIE Vol. 2726, 734:753	
		van Schoot, 0.7 NA DUV Step and Scan System for 150nm Imaging with Improved Overlay, SPIE Vol. 3679, 448:463, 1999	
		Yost et al., Lens Matching and Distortion Testing in a Multi-Stepper, Sub-Micron Environment, SPIE Vol. 1087, 233:244, 1989	
		Zavec, Life Beyond Mix-and-Match: Controlling Sub-0.18 Micron Overlay Errors, Semiconductor International, July 2000	
		Zavec, "Machine Models and Registration", SPIE Critical Reviews of Optical Science and Technology, CR52:134-159 (1994)	
CY		Zych et al., Electrical Methods for Precision Stepper Column Optimization, SPIE Vol. 633, 98:105, 1986	

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